

Supplementary Information

Enhanced photoresponse of epitaxially grown ZnO by MoO₃ surface functionalization

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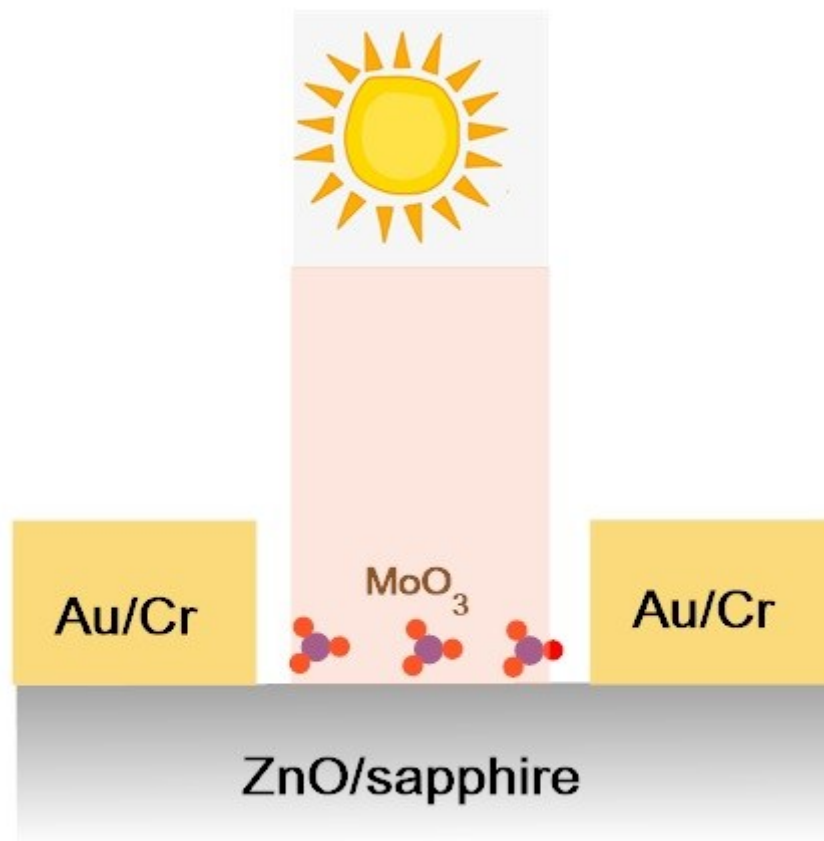


Figure S1 Schematic device structure of MoO₃ modified ZnO

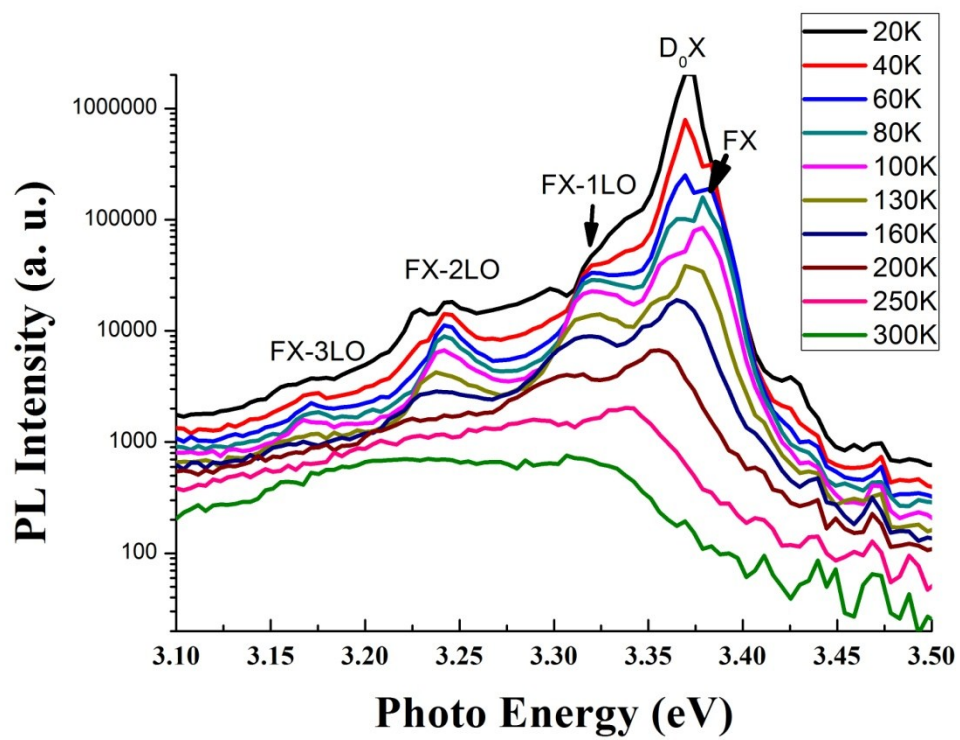


Figure S2 Temperature dependent PL spectra of 0.5 nm modified ZnO

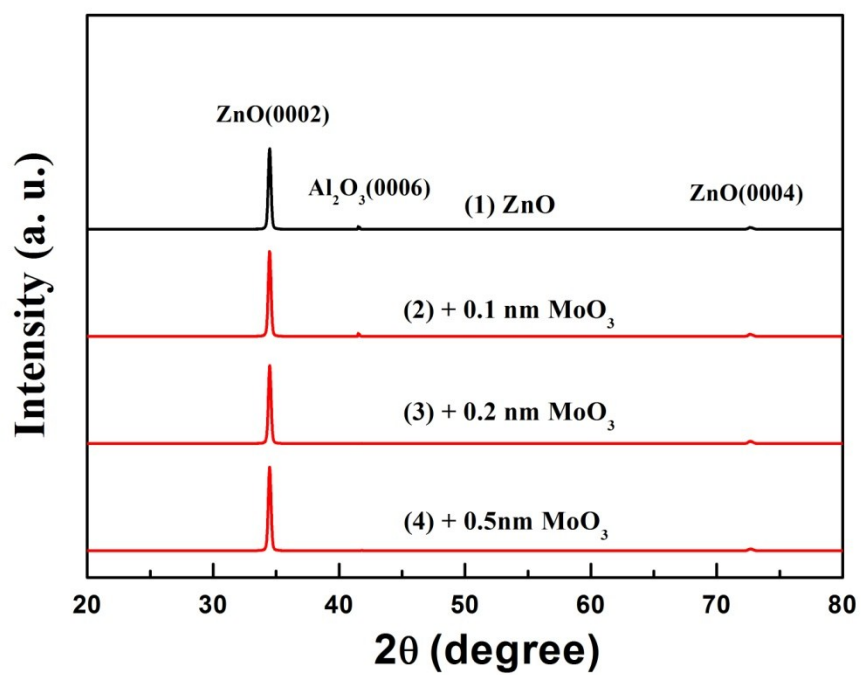


Figure S3 XRD spectra of ZnO thin film before and after the sequential deposition of 0.5 nm MoO₃.

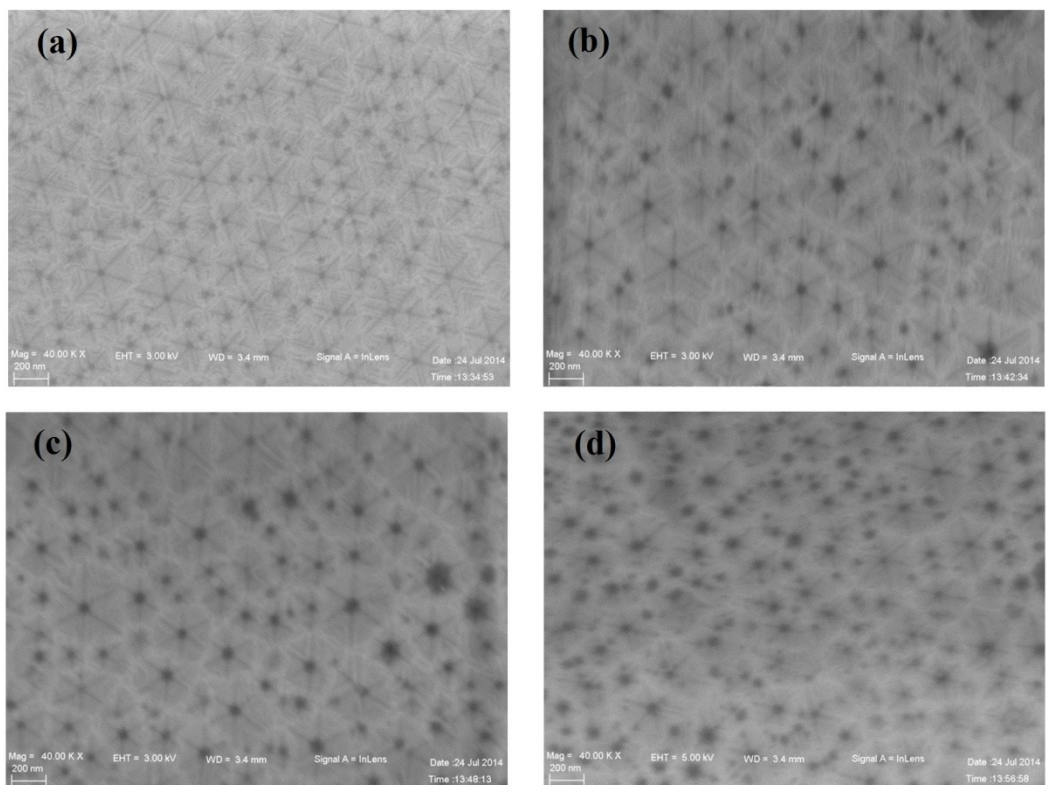


Figure S4 SEM images of (a) pristine ZnO and after (b) 0.1, (c) 0.2, and (d) 0.5 nm MoO_3 modification.